# GUJARAT TECHNOLOGICAL UNIVERSITY

BE - SEMESTER-V (NEW) EXAMINATION - SUMMER 2024

Subject Code:3151105 Date:23-05-2024

**Subject Name:VLSI Design** 

Time:02:30 PM TO 05:00 PM Total Marks:70

#### **Instructions:**

- 1. Attempt all questions.
- 2. Make suitable assumptions wherever necessary.
- 3. Figures to the right indicate full marks.
- 4. Simple and non-programmable scientific calculators are allowed.

### **MARKS**

- Q.1 (a) Compare semicustom and Full custom VLSI design style.
  - (b) Discuss following approaches used to reduce complexity of IC design
    i) Hierarchy ii) Regularity iii) Modularity iv) Locality
  - (c) Draw and explain various fabrication steps for CMOS inverter with proper notations at each fabrication steps.
- Q.2 (a) Explain MOSFET capacitance in brief.

03

07

- (b) Derive the drain current equation for MOSFET using Gradual Channel Approximation (GCA)
- (c) Find the depletion layer width, depletion region charge and threshold voltage with no substrate bias with the following physical parameters. Physical parameters

VSB=0, for silicon gate n channel MOS transistor, with the following parameters:

Substrate doping density NA=1.5 x 10<sup>16</sup> cm<sup>-3</sup>,

Gate donor doping  $N_D = 10^{18} \text{ cm}^{-3}$ ,

Gate oxide thickness to  $x = 400 \text{A}^{\circ}$ ,

 $Nss = 10 \times 10^{10} \text{ cm}^{-3}$ .

Consider Boltzmann Constant =  $1.38 \times 10^{-23}$  (J/K),

Electron charge =  $1.6 \times 10^{-19} \,\mathrm{C}$ ,

Intrinsic Silicon carrier concentration ni= 1.45 x 10<sup>10</sup> cm<sup>-3</sup>,

 $\varepsilon_{\rm S}i = 1.035 \text{ x } 10^{-12} \text{ F/cm}$ 

 $\varepsilon_0 = 8.85 \text{x} 10^{-14} \text{ F/cm},$ 

 $\varepsilon ox = 0.345 \times 10^{-12} \text{ F/cm}.$ 

#### OR

(c) For an enhancement type NMOS transistor has its source terminal connected to ground and 3 V connected to ground and 3 V connected to the gate. NMOS has  $V_T \! = \! 2$  V ,  $\lambda \! = \! 0.04$  1/V ,  $\mu_n$  \*Cox=20A/V², W= 200 $\mu$ m and L=10 $\mu$ m , VG= 3V , VD=0.5 V and 1 V. Calculate Drain Current  $I_D$ .

## **Physical constants:**

Thermal voltage =KT/q = 0.026 volt.

Energy Gap of silicon (Si) = $E_g = 1.12 \text{ Ev}$ .

Intrinsic Carrier Concentration of silicon=n<sub>i</sub>=1.45x10<sup>10</sup>cm<sup>-3</sup>.

Dielectric constant of vaccume = $\varepsilon_0$ =8.85 x 10-<sup>14</sup>F/cm.

Dielectric constant of silicon  $=\varepsilon_{si}=11.7 \text{ x}\varepsilon_0\text{F/cm}$ .

Dielectric constant of silicon dioxide = $\varepsilon_{ox}$ = 3.97  $x\varepsilon_{o}$ F/cm

### Q.3 (a) What is meant by static and dynamic power dissipation?

**07** 

(b) Define propagation delay and derive the expression for τpHL for 04 CMOS inverter. Assume ideal step as an input to CMOS inveter. 07 Consider a resistive load inverter circuit with  $V_{DD}=5$  V, Kn' =10 $\mu$ A/V<sup>2</sup>  $V_{TO}$ =0.8V,RL=400k $\Omega$  and W/L=2.Calculate the critical Voltages (V<sub>OH</sub>, V<sub>OL</sub>, V<sub>IL</sub> and V<sub>IH</sub>) on the VTC and find the noise margins of the circuit. OR Q.3Draw CMOS inveter. Explain its voltage transfer characteristic. Also 03 explain the NML and NMH noise margins with respect to this transfer characteristic 4.4.13 04 (b) Draw the inverter circuit with depletion type nMOS load. Mention the operating regions of driver and load transistors for different input voltages. Derive critical voltage points V<sub>OH</sub>, V<sub>OL</sub>, V<sub>IH</sub> and V<sub>IL</sub> for depletion- load nMOS inverter Consider a CMOS inverter with the following parameters: **07**  $VDD=3.3 \text{ V}, VT0, n=0.6 \text{ V}, VT0, p=-0.7 \text{ V}, kn=200 \mu\text{A/V}^2$  and  $kp = 160 \ \mu A/V^2$ Calculate the noise margins of the circuit. Consider kR=2.5 V and  $V_{T0,\neq}|V_{T0,p}|$  as it is not a symmetric CMOS inverter. **Q.4** What are the limitations of Dynamic circuits? Discuss the effect of 03 charge sharing and charge leakage in dynamic pass transistor logic. (b) Two nMOS transistors (M1 and M2) connected in series is shown in 04 Figure 1. The power supply is VDD =3.3 V and the nMOS threshold  $V_{TN} = 0.55 \text{ V}$ . Find the output voltage at node b. Consider i) Va = 2.7 Vand ii) Va = 3V.  $V_{DD}$ Figure 1 **07** Explain the Euler path approach to find the optimized stick-diagram for any CMOS logic circuit. Draw the optimized stick-diagram for the following Boolean function (CMOS Logic), F= (A(D+E)+ BC)'. Explain the importance of Euler path approach. What do you mean by stick diagram? Implement the following Boolean 03 **Q.4** function using stick diagram. Y = (A\*(D+E)+B\*C)'Explain the need of Voltage bootstrapping? Derive the mathematical 04 expression for dynamic Voltage bootstrapping circuit. For the Exclusive OR function, draw with following realization 07 1. Static CMOS realization 2. Pseudo nMOS gate 3. CMOS Transmission Gate(TG) 03 Q.5 (a) Compare FinFET and Planner MOSFET Draw transistor level circuit diagram of NAND based SR latch using 04 CMOS.

	<b>(c)</b>	What is clock-skew? Explain on-chip clock generation and distribution.	07
		OR	
Q.5	(a)	Draw and discuss three stage ring oscillator	03
	<b>(b)</b>	Implement and Describe CMOS clocked SR flip-flop	04
	(c)	What is need of Design of Testability (DFT) in VLSI IC design and explain Built in Self Test (BIST) techniques of DFT	07

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